Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	50	("4914056" "6091097" "4857141" "5508218" "5578524" "5670806" "5939748" "6083824" "6087675" "6165880" "6204561" "4443933" "4519126" "4562640" "4775550" "4778560" "5362661" "5376227" "5414655" "5444020" "5449635" "5482886" "5500384" "5607874" "5607873" "5652165" "5686342" "5700349" "5702989" "5714780" "5719418" "5759888" "5814526" "5877075" "5903430" "5928967" "5930630" "5935762" "5973361" "5976968" "5976984" "5990555" "6004729" "6018184" "6049104" "6048759" "6063711" "6077733" "6084312" "6103598").pn.	USPAT	OR	ON	2005/11/17 17:53
S2	73983	contact adj hole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 12:35
S3	6473	second adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 12:38
S4	19510	etch adj stop	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2005/11/07 12:38
S5	19	S2 and S3 and S4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 12:38
S6	6737	sidewall near4 nitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 15:56

S7	6473	second adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 17:05
S8	31	S7 and S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:37
S9	37	2nd adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 16:06
S10	1151305	sidewall or side adj wall	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 17:05
S11	299478	nitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2005/11/07 17:05
S12	58054	S10 and S11	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2005/11/07 17:06
S13	239	S12 and S7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 17:06
S14	1603003	semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/07 17:06

S15	231	S13 and S14	US-PGPUB;	OR	ON	2005/11/08 08:52
			USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB			
S16	19525	etch adj stop	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52
S17	6479	second adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52
S18	1151533	sidewall or side adj wall	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52
S19	299616	nitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52
S20	58105	S18 and S19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52
S21	239	S20 and S17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52
S22	1603408	semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52

			T			
S23	231	S21 and S22	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 08:52
S24	27	S16 and S23	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 09:02
S25	11254	etch adj stop adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT;	OR	ON	2005/11/08 09:02
S26	4153	S18 and S19 and S25	IBM_TDB US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2005/11/08 09:02
S27	3917	S22 and S26	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 09:02
S28	22	S17 and S27	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 10:01
S29	239	S18 and S19 and S17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 09:43
S30	27	S16 and S17 and S18 and S19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 10:03

8/3/2006 4:16:38 PM C:\Documents and Settings\qjefferson\My Documents\EAST\Workspaces\10750001.wsp Page 4

S31	22	S25 and S17 and S18	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 10:03
S32	209176	insulating adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 10:26
S33	2681	S25 and S19 and S32	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/08 10:26
S34	11288	etch adj stop adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:38
S35	300140	nitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:38
S36	2688	S34 and S35 and insulating adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:39
S37	6485	second adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 08:00
S38	27	S37 and S36	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:41

S39	4530	S34 same S35	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:41
S40	259916	(insulation or insulating) adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:41
S41	799	S39 same S40	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:43
S42	781	nitride adj oxide adj nitride or nitride-oxide-nitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:44
S43	1605694	semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:44
S44	600	S42 and S43	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 12:32
S45		S34 and S44	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 07:59
S46	37	2nd adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 12:33

S47	300140	nitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 12:33
S48	11288	etch adj stop adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 12:33
S49	6485	second adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 12:33
S50	47	(S46 or S49) and S48 and S47	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 13:58
S51	86799	barrier adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 13:58
S52	6485	second adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 13:58
S53	210	S52 and S51	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 15:03
S54	2	10/452347.app.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 15:13
S55	5	("20020064945" "20030122174" "5591675" "5731236" "6413816").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/15 16:18

S56	0	("6852592").URPN.	USPAT	OR	ON	2005/11/15 15:11
S57		"20010055840"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/16 09:27
S58	2	"6013937".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:09
S59	1316478	HF or hydrogen fluoride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:12
S60	319588	BOE or buffered adj oxide adj etchant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:14
S61	797668	cleaning	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:10
S62	32866	S61 same (S59 or S60)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:10
S63	1605694	semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:11
S64	10307	S62 and S63	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:11

S65	1045	S61 and S60 and S63	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2005/11/15 17:11
S66	755 ·	S65 and S59	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:11
S67	171575	HF or hydrogen adj fluoride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:12
S68	487	S61 and S63 and S60 and S67	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:13
S69	786	buffered adj oxide adj etchant	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:14
S70	478	S67 and S69	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:14
S71	439	S63 and S70	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:14
S72	166	S71 and S61	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:20

S73	18686	contact adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:21
S74	561	S52 and S73	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:21
S75	178	S74 and S63	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:22
S76	13406	storage adj node	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:22
S77	49	S75 and S76	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2005/11/15 17:24
S78	2072	storage adj node adj contact	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:25
S79	396	storage adj node adj contact adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:29
S80	168674	gate adj electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:29

S81	139	S79 and S80	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 18:15
S82	2	"5631185".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 17:42
S83	7	"2004009656"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 18:15
S84	2	"20040009656"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/15 18:15
S85	1	10/750001.app.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/16 09:27
S86	2	"6852592".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/16 16:04
S87	5	("20020064945" "20030122174" "5591675" "5731236" "6413816").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/11/16 16:24
S88	0	("6852592").URPN.	USPAT	OR	ON	2005/11/16 16:21
S89	2	"6239026".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/16 16:24

S90	2	"6511904".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO;	OR	ON	2005/11/16 16:26
			DERWENT; IBM_TDB			
S91	1	2003-068879	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/16 16:26
S92	4	"2003068879"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/16 16:27
S93	0	"1020010077518"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/16 16:27
S94	185	tantalum adj oxynitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 08:52
S95	64758	cmp or chemical adj mechanical adj polishing	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 08:15
S96	30	S94 and S95	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 09:13
S97	12677	electromigration or electro-migration	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 08:16

						
S98	3	S94 and S97	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 08:17
S99	1622006	copper or cu	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 08:16
S10 0	58	S94 and S99	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 08:18
S10 4	2	"6111744".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 08:57
S10 5	2	"5916359".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 09:13
S10 6	2	"6110529".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 09:14
S10 7	2	"6203613".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 09:15
S10 8	121374	aluminum adj oxide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 09:15

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S10 9	783	nitride adj oxide adj nitride	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 09:15
S11 2	76	S108 and S109	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 10:23
S11 3	2	"4766093".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 09:34
S11 4	2	"6740553".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 11:52
S11 5	1	10/750001	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 15:33
S11 6	.0	2002/0074583	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 15:33
S11 7	2	"20020074583"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 15:34
S11 8	2	"20020074582" ·	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 15:56

			T.,,			2005/44/45 45 55
S11 9	2	"6696336".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 15:57
S12 0	90321	barrier adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:27
S12 1	32	(interlaying or inter-laying or inter adj laying) adj (insulating or interlation) adj (layer or film or liner)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:46
S12 2	. 0	removing adj remnants near4 planarization	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/03/20.09:46
S12 3	3	cleaning near remove near4 planarization	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:47
S12 4	12248	(cmp or chemical adj mechanical adj polishing) near4 planarization	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:48
\$12 5	9270	(cmp or chemical adj mechanical adj polishing) near2 planarization	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:48
S12 6	628	(cmp or chemical adj mechanical adj polishing) near2 planarization near4 (remove or removing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:54

S12 7	0	cleaning adj after adj planarizing	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:54
S12 8	0	cleaning adj after near2 planarizing	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:54
S12 9	0	cleaning adj after near2 (planarizing or planarization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:55
S13 0		cleaning adj after near4 (planarizing or planarization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 09:55
S13 1	719	cleaning near4 (planarizing or planarization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/20 11:01
S13 2	719	cleaning near4 (planarizing or planarization)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2006/03/20 12:26
S13 3	13213	etch adj stop adj (layer or liner or film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 07:54
S13 4	40421	interlayer adj insulat\$4 adj (layer or liner or film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 07:55

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S13 5	801641	plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 07:55
S13 6	105850	barrier adj (layer or liner or film)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 07:55
S13 7	97	S133 and S134 and S135 and S136	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 07:55
S13 8	804	438/597.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 10:25
S13 9	2	"6696336".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 09:28
S14 0	20	("4656732" "5144579" "5338700" "5401681" "5834845" "5843830" "5844771" "5869861" "5956594" "5989952" "6046093" "6100137" "6127260" "6134137" "6140172" "6168984" "6187624" "6221711" "6251726" "6300191").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/03 09:39
S14 1	32	etch adj stop adj (layer or liner or film) near7 (ono or oxide adj nitride adj oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 09:40
S14 2	86	(first near1 plug) near7 (electrically near1 connected) near7 (second near1 plug)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 09:47

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S14 3	234	(first near2 plug) near7 (electrically near1 connected) near7 (second near2 plug)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 09:46
S14 4	36	semiconductor and S142	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 09:47
S14 5	137	semiconductor and S143	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 10:08
S14 7	2	09/930144.app.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/08/03 10:09
S14 8	2	("5520992" "6222722").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/08/03 10:09
S14 9	6512	first near1 plug and second near1 plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 10:25
S15 0	4200	first adj plug and second adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 10:26
S15 1	12938	etch adj stop adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 10:26
S15 2	47	S149 and S150 and S151	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 10:29

S15 3	319	first adj conductive adj plug and second adj conductive adj plug	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/03 10:30
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